NATIONAL UNIVERSITY OF SINGAPORE

Do	c No. CIBA/RA/Exp/023									
Ту	pe: Experiment / Equipment		Acti	vity-Based Risk Assessment Fo	rm					
Name of Department		Physics		_Location of Lab		S07-01-09				
Name of Laboratory		CIBA chemistry lab		Name of PI		Mark Breese				
Name of Researcher/LO Dang Zhiya			hiya	Name of Activity/Experiment		Removal of Protek photoresist				
1. Hazard Identification			2. Access the Ris		sk 3. F			Risk Control		
No	Description/Details of Steps in Activity	Hazards	Possible Accident / III Health & Persons-at-Risk	Existing Risk Control (Mitigation)	Severity	Likelihood (Probability)	Risk Level	Additional Risk Control	Person Responsible	By (Date)
1	Prepare Piranha solutions	oxidizer. Contact with other material may cause a fire. Hydrogen peroxide (H2O2), harmful by inhalation, in contact with skin and if swallowed. 2) hot surface of the containers	Acid spill, explosion could occur if the H2O2 is at 50% or greater, or the concentrated H2SO4 is added into the H2O2 first.	Users need additional protective equipment include: a full face shield, heavy duly rubber gloves. Only use glass containers(preferably pyrex). Move any organic compounds away from the fume hood which could induce fire while reacting with the solution. Only trained and authorized personnel are allowed to use the piranha etching solution.	2	1	2		Dang Zhiya	10/9/2010
2	Removal of Protek photoresist	Corrosive and caustic Piranhna etching solution.	Piranhna etching solution spillage.	Wear protective equipment and only use in fume hood.	2	1	2		Dang Zhiya	10/10/2010
3	Storage of the waste piranha solution.	Chemical	A hot solution in a tight container might explode due to the gas generation due to the gas generation and over pressurization of the container.	Never store the hot piranhna solution. Cool down the solution for several hours and dilute it before a proper storage.	2	1	2		Dang Zhiya	10/11/2010
5							0			
6				 			0			
7							0			
8			1	1			0			
	Conducted By		Dang Zhiya	Approved By						
				Name			Mark Breese			
				Signature						
				Approval date				Next Revision date (Maximum 3 years)		

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